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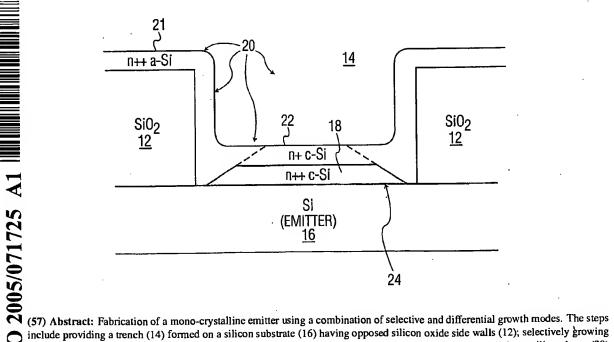
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(54) Title: METHOD OF FABRICATING A MONO-CRYSTALLINE EMITTER



include providing a trench (14) formed on a silicon substrate (16) having opposed silicon oxide side walls (12); selectively growing a highly doped mono-crystalline layer (18) on the silicon substrate in the trench; and non-selectively growing a silicon layer (20) over the trench in order to form an amorphous polysilicon layer over the silicon oxide sidewalls.

Deciarations under Rule 4.17:

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 as to the applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii)) for all designations

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